Attorney Docket No. H1508

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Christine Hau-Riege, et al. : Group Art Unit: Not yet assigned

Serial No.: 60/501,445 : Examiner: Not yet assigned

Filed: September 9, 2003

Title: SEMICONDUCTOR COMPONENT AND METHOD FOR PRECLUDING STRESS-

INDUCED VOID INFORMATION IN THE SEMICONDUCTOR COMPONENT

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Attached hereto is a completed Form PTO-1449 listing patents, publications, or other information which the applicant believes may be material to the examination of this application, with copies of each such item enclosed herewith. It is requested that the cited patents be made of record in the examination of this application. This information disclosure statement is being filed prior to the first Office Action and no certification or fee is required. The commissioner is authorized to charge any fee deficiency required by this paper or credit any overpayment to Deposit Account No. 50-2173. A duplicate of this communication is enclosed.

Respectfully submitted.

Dated: 29 Oct 2003

By Jøhn D. Titus, Reg. No. 39,047

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT			APPLICANT Christine Hau-Riege, et al.			
			U.S. PATENT DOCUME	ENTS		
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	6,245,996	06/12/01	Atakov,et al.			- 1 -
	2001/0001427	05/24/01	Atakov, et al.			
d. 131 11						
		FORE	IGN PATENT DOC	UMENTS		
DOCUMENT NUMBER		DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION
						YES NO
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		<u> </u>	<u></u>			
	OTHER DOC	UMENTS (I	ncluding Author, Ti	tle, Date Perti	inent Pages, Et	c.)
	Ogawa, E.T., et al., Stress-Induced Voiding Under Vias Connected To Wide Cu Metal Leads,					
<u>,</u>						
EXAMINER .						DATE CONSIDERED

EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.